

Introduction

The special issues of this Journal produced to mark the appearance of Volumes 100 (1975), 200 (1980) and 300 (1986) are very well known to organometallic chemists, and such 'centenary' issues are so much an established feature of organometallic chemistry that little introduction to Volume 400 is needed.

In line with the procedure used for the earlier 'centenary' volumes, for Volume 400, all the members of the Editorial Board and those authors who contributed to Volume 300 were invited to submit the names of up to 15 chemists (excluding those who contributed to Volumes 100, 200 or 300) whom they considered to have made the most meritorious contributions to organometallic chemistry. The authors receiving the most nominations were invited to contribute to the celebratory issue, and an excellent response resulted in the collection of the 19 reviews presented in this volume.

As before, contributors were invited to review some aspect of their own work in any form they wished, and as in the case of the previous 'centenary' volumes some chose to survey a specific area of their current studies and others to outline the development of their researches over a number of years, with some emphasis on personal aspects. The volume is being made widely available, and will be of interest to students as well as to established organometallic chemists. The 'centenary' volumes taken together will also be of interest in the future as an indication of which chemists were judged by their peers to have made the most important contributions to organometallic chemistry in the past 40 years or so. They will in addition provide a record of the development of activity in the subject in various parts of the world, and in this respect a notable feature of the present volume is the large number of contributors based in France or Germany.

The Regional Editors and the Publisher are grateful to those who submitted nominations and those who contributed reviews. They also take the opportunity to thank authors, referees, and readers for their continuing support of the Journal.

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